

Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

Claims 1-8 (Cancelled).

9. (Currently Amended) A shower plate having a plurality of ejection holes adapted to eject a gas, said shower plate characterized in that having a diameter of the ejection hole on the side where the gas flows out of the hole is twice or less a plasma sheath thickness.

10. (Currently Amended) A shower plate according to claim 9, characterized in that wherein a diameter of the ejection hole is changed from the side where the gas flows into the hole toward the side where the gas flows out of the hole.

11. (Currently Amended) A shower plate according to claim 10, characterized in that wherein the diameter on the side where the gas flows out of the hole is not less than 0.02mm and is not more than 10mm.

12. (Currently Amended) A shower plate having a plurality of ejection holes adapted to eject a gas, said shower plate characterized in that the wherein each ejection hole has a portion, on the side where the gas flows into the hole, having a width which is more than 0.5mm and is not more than 5mm and a portion, on the side where the gas flows out of the hole, having a width which is not less than 0.02mm and is not more than 0.5mm.

13. (Currently Amended) A shower plate according to claim 12, characterized in that wherein said portion having the width which is not less than 0.02mm and is not more than 0.5mm has a length of 0.2mm to 2mm.

14. (Currently Amended) A shower plate according to claim 13, characterized in that wherein said shower plate has a thickness of at least 20mm.

15. (Currently Amended) A shower plate having a plurality of ejection holes adapted to eject a gas, said shower plate characterized in that wherein a fluctuation in hole

diameter of the ejection holes on the side where the gas flows out of the holes is not more than 1% over the entire shower plate.

16. (Currently Amended) A shower plate according to claim 15, ~~characterized in that wherein~~ the fluctuation in hole diameter of the ejection holes on the side where the gas flows out of the holes is not more than 0.25% over the entire shower plate.

17. (Currently Amended) A shower plate according to ~~any one of claims 1 through 15~~ claim 9, ~~characterized in that wherein~~, of both surfaces of said shower plate, at least the surface on the side where the gas flows out is not a flat surface.

18. (Currently Amended) A shower plate according to claim 12, ~~characterized in that wherein~~ the peripheral portion of the surface of said shower plate on the side where the gas flows out is projected over the center portion thereof.

19. (Currently Amended) A shower plate according to claim 12, ~~characterized in that wherein~~ the peripheral portion of said shower plate has a thickness greater than that of the center portion.

20. (Currently Amended) A shower plate ~~having a plurality of ejection holes adapted to eject a gas, said shower plate according to claim 10,~~ ~~characterized in that wherein~~ a center axis of at least a portion, on the side where the gas flows out, of each of at least part of said plurality of ejection holes is inclined with respect to a normal of a surface, which is to face an object to be processed, of at least a center portion of said shower plate.

21. (Currently Amended) A shower plate according to claim 20, ~~characterized in that wherein~~ inclination of said center axis is set such that the gas is ejected from said at least part of said plurality of ejection holes in a direction towards the center of said shower plate and in a direction towards the side where the object to be processed is to be placed.

22. (Currently Amended) A shower plate ~~having a plurality of ejection holes adapted to eject a gas, said shower plate according to claim 2,~~ ~~characterized in that wherein~~ means for introducing the gas from the exterior to a surface of said shower plate on the side

where the gas flows into said ejection holes is provided at a peripheral portion of said shower plate.

Claims 23-27 (Canceled).

28. (Currently Amended) A plasma processing apparatus characterized by comprising the shower plate according to any one of claims ~~1 to 22~~ 9, 12, and 22.

29. (Currently Amended) A product manufacturing method characterized by comprising carrying out a process using the shower plate according to any one of claims 9, 12, and 22, thereby manufacturing a product semiconductor device.

Claims 30 and 31 (Canceled).

32. (New) A product manufacturing method comprising carrying out a process using the shower plate according to any one of claims 1, 4, and 14, thereby manufacturing a liquid crystal display device or an organic EL display device.